

<b>INFORMATION DISCLOSURE CITATION</b> <i>(Use several sheets if necessary)</i>	<b>Docket Number (Optional)</b> <b>TWI-30510</b>	<b>Application Number</b> <b>NEW</b>
	<b>Applicant(s)</b> <b>Kenneth C. Johnson et al.</b>	
	<b>Filing Date</b> <b>HEREWITH</b>	<b>Group Art Unit</b> <b>Unknown</b>

### U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE
CS	*BF	6,541,287	04/01/2003	Ino et al.	438	16	03/03/1999
	*BG	6,542,829	04/01/2003	Gupta	703	33	09/21/2000
	*BH	2002/0005957	01/17/2002	Finarov et al.	356	630	08/31/2001
	*BI	2002/0033945	03/21/2002	Xu et al.	356	369	09/21/2001
CS	*BJ	2002/0192847	12/19/2002	Ino et al.	438	14	07/29/2002

### FOREIGN PATENT DOCUMENTS

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO

### OTHER DOCUMENTS

*(Including Author, Title, Date, Pertinent Pages, Etc.)*

CS	*BK	R.H. Krukar et al., "Using Scattered Light Modeling for Semiconductor Critical Dimension Metrology and Calibration," <i>SPIE</i> , Vol. 1926 (1993), pp. 60-71.					
	*BL	C.J. Raymond et al., "A Scatterometric Sensor for Lithography," <i>SPIE</i> , Vol. 2336 (1994), pp. 37-49.					
	*BM	C.J. Raymond et al., "Metrology of Subwavelength Photoresist Gratings Using Optical Scatterometry," <i>J. Vac. Sci. Technology B</i> , Vol. 13, No. 4, July/Aug. 1995, pp. 1484-1495.					
	*BN	M.R. Murnane et al., "Scatterometry for 0.24 $\mu\text{m}$ - 0.70 $\mu\text{m}$ Developed Photoresist Metrology," <i>SPIE</i> , Vol. 2439 (1995), pp. 427-436.					
	*BO	M.R. Murnane et al., "Subwavelength Photoresist Grating Metrology Using Scatterometry," <i>SPIE</i> , Vol. 2532, (1995), pp. 251-261.					
	*BP	C.J. Raymond et al., "Multi-Parameter Process Metrology Using Scatterometry," <i>SPIE</i> , Vol. 2638 (1995), pp. 84-93.					
	*BQ	J. Bischoff et al., "Photoresist Metrology Based on Light Scattering," <i>SPIE</i> , Vol. 2725 (1996), pp. 678-689.					
	*BR	C.J. Raymond et al., "Multi-Parameter CD Measurements Using Scatterometry," <i>SPIE</i> , Vol. 2725 (1996), pp. 698-709.					
	*BS	C.J. Raymond et al., "Scatterometry for CD Measurements of Etched Structures," <i>SPIE</i> , Vol. 2725 (1996), pp. 720-728.					
	*BT	B.K. Minhas et al., "Towards Sub - 0.1 $\mu\text{m}$ CD Measurements Using Scatterometry," <i>SPIE</i> , Vol. 2725 (1996), pp. 729-739.					
	*BU	J. Bischoff et al., "Light Scattering Based Micrometrology," <i>SPIE</i> , Vol. 2775 (1996), pp. 251-259.					
	*BV	X. Niu, "Specular Spectroscopic Scatterometry in DUV Lithography," <i>SPIE</i> , Vol. 3677 (1999), pp. 159-168.					
	*BW	J. Allgair et al., "Manufacturing Considerations for Implementation of Scatterometry for Process Monitoring," <i>SPIE</i> , Vol. 3998 (2000), pp. 125-134.					
	*BX	L. Li, "Formulation and Comparison of Two Recursive Matrix Algorithms for Modeling Layered Diffraction Grating," <i>Journal of the Optical Society of America</i> , Vol. A 13, No. 5, May 1996, pp. 1024-1035.					
	*BY	<i>Handbook of Optics</i> , 2nd Edition, Vol. 2, <i>Optical Society of America</i> (1995), Chapter 22 entitled "Polarimetry," pp. 22.1-22.37.					
CS	*BZ	<i>Handbook of Optics</i> , 2nd Edition, Vol. 2, <i>Optical Society of America</i> (1995), Chapter 27 entitled "Ellipsometry," pp. 27.1-27.27.					

<b>Examiner</b> <i>Calvin M. Z.</i>	<b>Date Considered</b> <i>7/14/04</i>
<b>Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</b>	

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### U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE
CSJ	*AA	4,689,754	08/25/1987	Collins et al.	702	32	02/21/1985
	*AB	4,757,207	07/12/1988	Chappelow et al.	250	491.1	03/03/1987
	*AC	4,885,709	12/05/1989	Edgar et al.	364	563	01/16/1987
	*AD	5,262,635	11/16/1993	Curbelo	250	214R	05/12/1992
	*AE	5,315,513	05/24/1994	Abreu et al.	702	3	10/29/1991
	*AF	5,428,558	06/27/1995	Cahill et al.	356	319	12/17/1993
	*AG	5,488,476	01/30/1996	Mansfield et al.	356	512	10/12/1994
	*AH	5,502,799	03/26/1996	Tsuji et al.	345	600	05/14/1993
	*AI	5,523,840	06/04/1996	Nishizawa et al.	356	355	06/21/1994
	*AJ	5,607,800	03/04/1997	Ziger	430	8	02/15/1995
	*AK	5,867,276	02/02/1999	McNeil et al.	356	445	03/07/1997
	*AL	5,884,684	12/01/1998	Maris et al.	356	432	02/28/1997
	*AM	5,905,822	05/18/1999	Ito et al.	382	300	07/15/1996
	*AN	5,963,329	10/05/1999	Conrad et al.	356	372	10/31/1997
	*AO	5,993,386	11/30/1999	Ericsson	600	300	07/15/1997
	*AP	6,037,614	03/14/2000	He et al.	257	184	03/06/1998
	*AQ	6,242,739	06/05/2001	Cherkassky	250	339.11	04/19/1999
	*AR	6,281,974	08/28/2001	Scheiner et al.	356	491	06/08/2000
	CSJ	*AS	6,476,920	11/05/2002	Scheiner et al.	356	630
*AT		6,485,872	11/26/2002	Rosenthal et al.	430	30	11/22/2000

### FOREIGN PATENT DOCUMENTS

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							YES	NO
CSJ	*AU	EP 72367 A	02/1983	EPC	G01B	15/02		
	*AV	EP 324490 A	07/1989	EPC	A61N	05/06		
CSJ	*AW	JP 08015036 A	01/1996	Japan	G01J	05/00		
	*AX	WO 99/45340	09/10/1999	PCT	G01B	11/02	X	

### OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

CSJ	*AY	G.H. Schut, "Review of Interpolation Methods for Digital Terrain Models," <i>The Canadian Surveyor</i> , Vol. 30, No. 5, December 1976, pp. 389-412.
	*AZ	W.S. Russell, "Polynomial Interpolation Schemes for Internal Derivative Distributions on Structured Grids," <i>Applied Numerical Mathematics</i> , Vol. 17 (1995), pp. 129-171.
	*BA	Book, <i>Numerical Recipes in C++ - The Art of Scientific Computing</i> , Second Edition, Cambridge University Press (2002), pp. 126-132.
	*BB	Printout, "GeoComputation 99 - What's the Point? Interpolation and Extrapolation with a Regular Grid DEM," (1999), 17 pages in length.
	*BC	<i>IBM Technical Disclosure Bulletin</i> , "Spectroscopic Pitch Measurement Technique," September 1989, pp. 391-392.
CSJ	*BD	<i>IBM Technical Disclosure Bulletin</i> , "Phase-Sensitive Overlay Analysis Spectrometry," March 1990, pp. 170-174.
	*BE	D.M. Haaland et al., "Partial Least-Squares Methods for Spectral Analyses - I. Relation to Other Quantitative Calibration Methods and the Extraction of Qualitative Information," <i>Anal. Chemistry</i> , Vol. 60, No. 11, June 1, 1988, pp. 1193-1202.

Examiner <i>Carl M. Z.</i>	Date Considered <i>7/14/04</i>
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